Chapter 4

Spin Valves

韩伟 量子材料科学中心 2018年11月9日

Outline 1 and 1 an

1. Spin valves and spin injection

2. Spin valves based on Metal and Superconductor

3. Spin valves based on semiconductor and Quantum materials

1. Metal Spin Valves

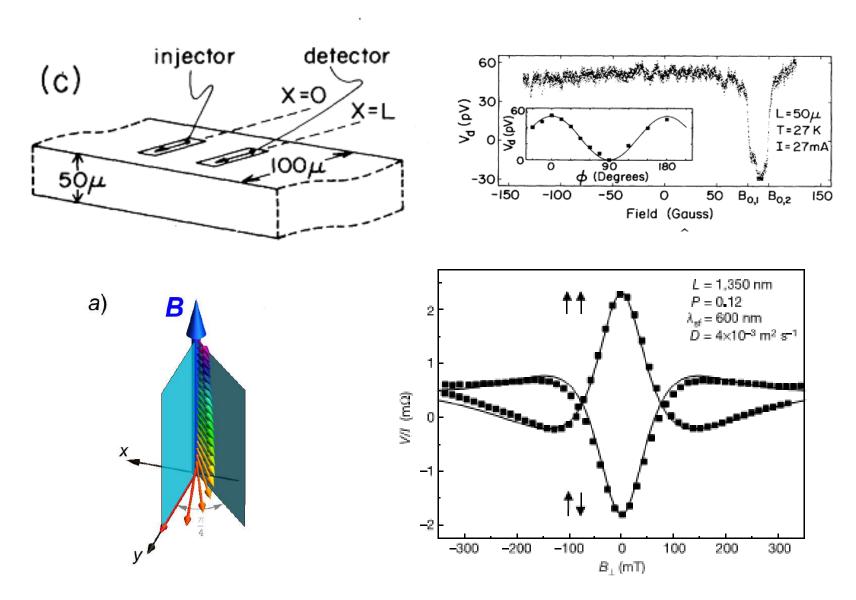
Local and Nonlcoal spin valves

Hanle spin precession

Nano devices (Thanks to cleanroom)

Spin injection efficiency

Spin relaxation in Metals: EY



Spin Injection efficiency

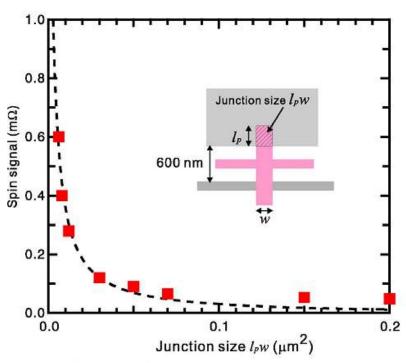
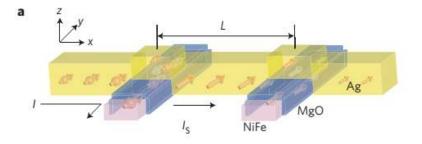
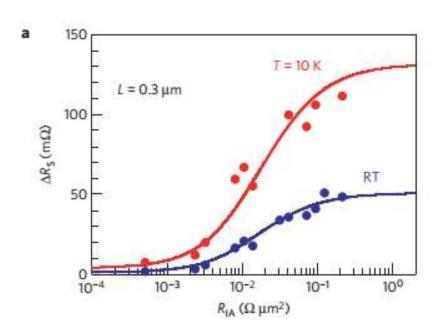
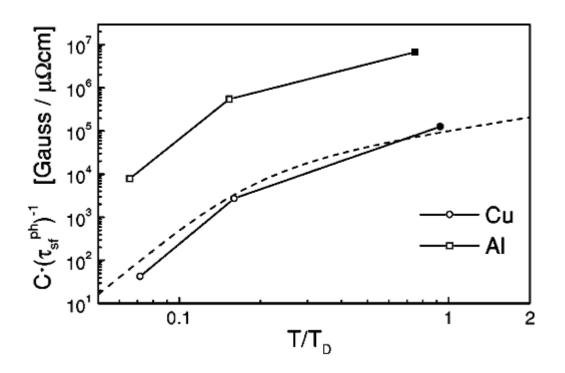


FIG. 4. (Color online) Spin signal in the NLSV measurement as a function of the junction size $l_p w$. The dotted curve is the best fitting to the data points using Eq. (2).







$$\frac{\tau_e}{\tau_{sf}} = a \propto \left(\frac{\lambda}{\Delta E}\right)^2$$

Jedema, et al, PRB (2003) Fabian & Das Sarma, PRL (1998)

Outline |

2. Superconductor Spin Valves

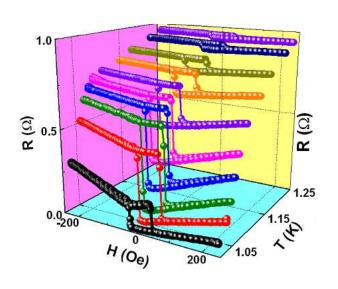
Large MR and control of T_C

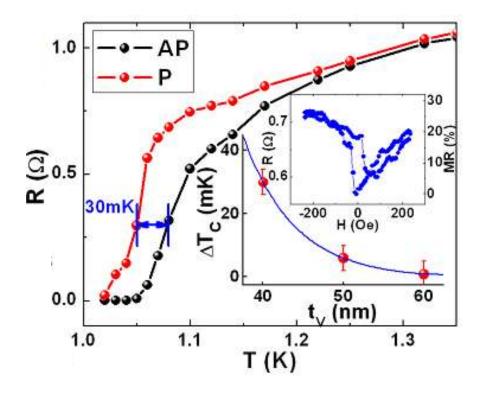
Josephson junction, Spin-triplet

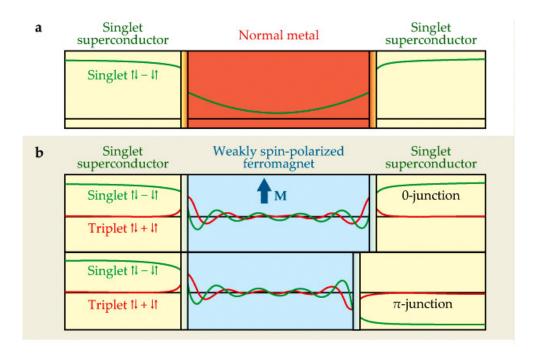
Spin injection, Long spin lifetime

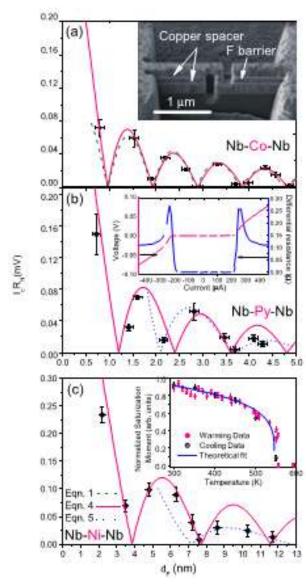
Large spin Hall

Dynamic spin injection: spin triplet pairs and SC coherence peak



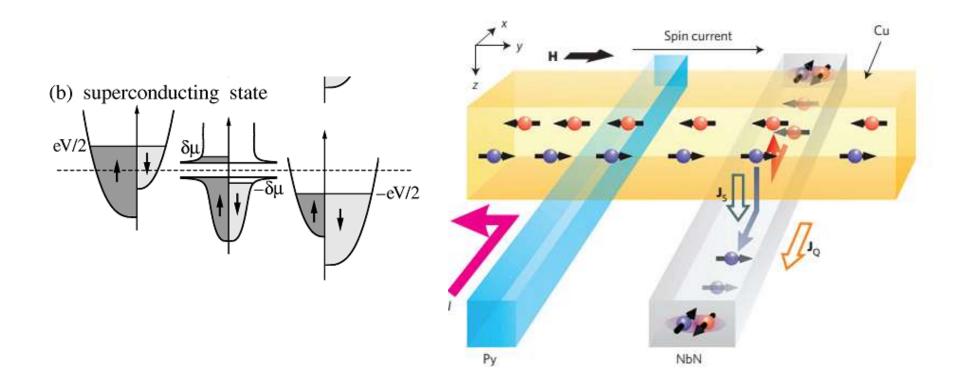




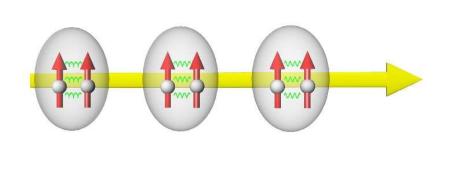


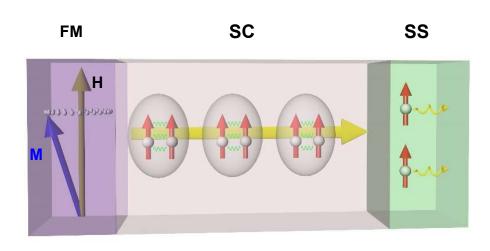
Spin injection

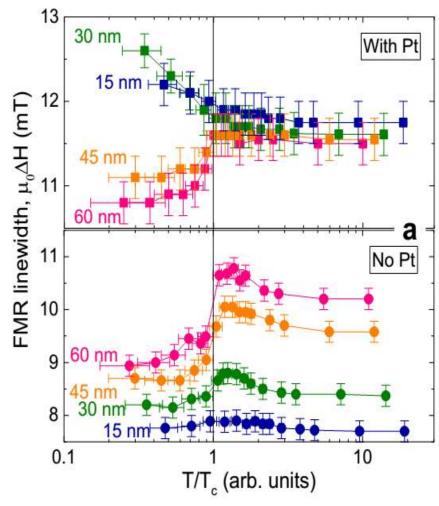
Spin Hall



Dynamic Spin injection







This Class

3. Spin valves based on Semiconductor and Quantum materials

Outline

1. Semiconductor Spin Valves

When spintronics meets semiconductor

GaAs

Silicon and Germanium

Complex oxides

Spin FET

Why semiconductor Spintronics

Magnetic materials

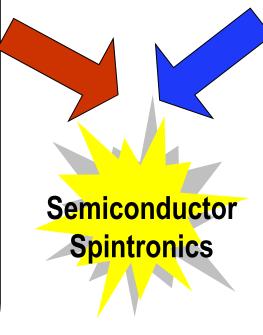
Information storage

- Hard disks
- Tapes
- MRAM

Advantages:

- Non-volatile
- Fast switching





Semiconductor

Information logic and computing

- Transistor
- CPU

Advantages:

- Tunable carrier densities
- Bipolar (electron/hole)



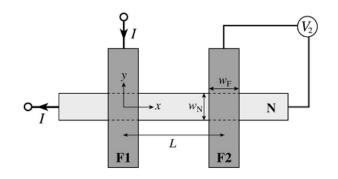
$$R_{NL} = 4R_N e^{-L/\lambda_N} \prod_{i=1}^{2} \left(\frac{P_J \frac{R_i}{R_N}}{1 - P_J^2} + \frac{P_F \frac{R_F}{R_N}}{1 - P_F^2} \right) \times \left[\prod_{i=1}^{2} \left(1 + \frac{2 \frac{R_i}{R_N}}{1 - P_J^2} + \frac{2 \frac{R_F}{R_N}}{1 - P_F^2} \right) - e^{-2L/\lambda_N} \right]^{-1}$$

$$P_F = (\sigma_F^{\uparrow} - \sigma_F^{\downarrow}) / (\sigma_F^{\uparrow} + \sigma_F^{\downarrow})$$

$$P_J = (G_i^{\uparrow} - G_i^{\downarrow}) / (G_i^{\uparrow} + G_i^{\downarrow})$$

$$R_{N} = \rho_{N} \lambda_{N} / A_{N}$$

$$R_{E} = \rho_{E} \lambda_{E} / A_{L}$$

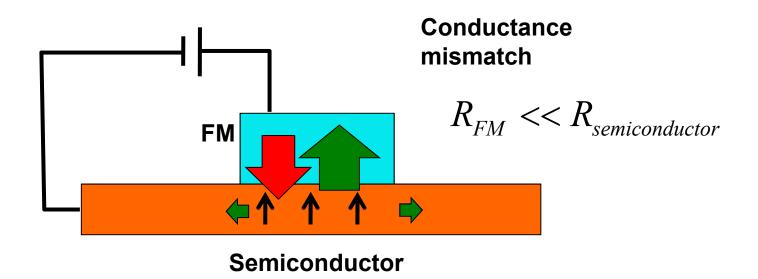


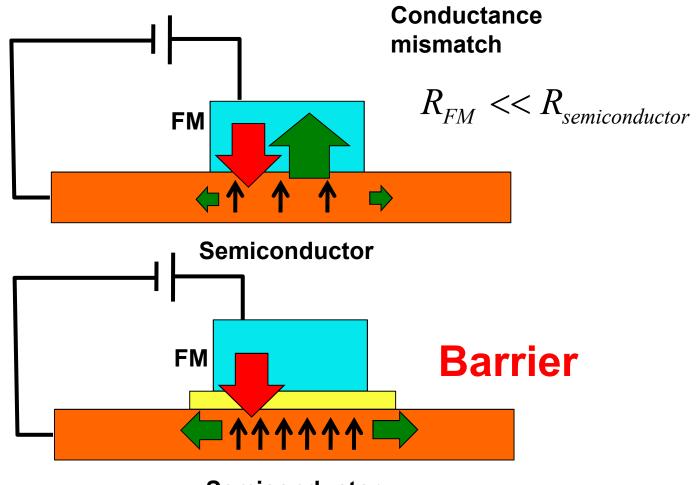
R_i (R₁, R₂) interficial resistances between FM (injector, detector) and nonmetal material.

$$R_{NL} = 4R_N e^{-L/\lambda_N} \prod_{i=1}^{2} \left(\frac{P_X \frac{R_i}{R_N}}{1 - P_J^2} + \frac{P_F \frac{R_F}{R_N}}{1 - P_F^2} \right) \times \left[\prod_{i=1}^{2} \left(1 + \frac{2 \frac{R_i}{R_N}}{1 - P_J^2} + \frac{2 \frac{R_F}{R_N}}{1 - P_F^2} \right) - e^{-2L/\lambda_N} \right]^{-1}$$

$$R_{NL} = \frac{4p_F^2}{(1-p_F^2)^2} R_N (\frac{R_F}{R_N})^2 \frac{e^{-L/\lambda_G}}{1-e^{-2L/\lambda_G}} = \frac{4p_F^2}{(1-p_F^2)^2} \frac{R_F^2}{R_N} \frac{e^{-L/\lambda_G}}{1-e^{-2L/\lambda_G}}$$

$$P^2 = \frac{4p_F^2}{(1-p_F^2)^2} (\frac{R_F}{R_N})^2$$





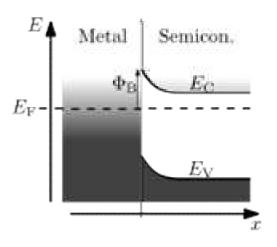
Semiconductor

E.I. Rashba, Phys. Rev. B (2000)

A. Fert, H. Jaffres, Phys. Rev. B (2001)

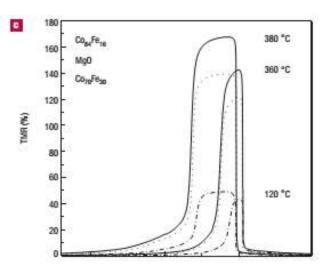
Two types of tunnel barrier

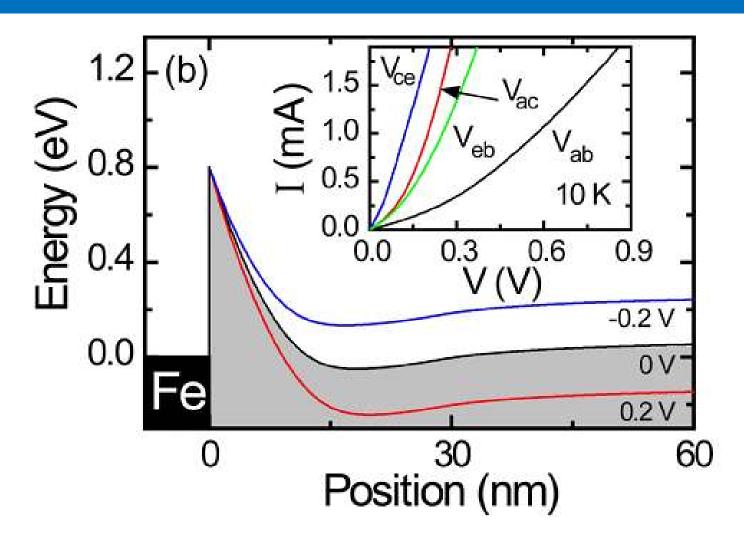
1) Schottky barrier



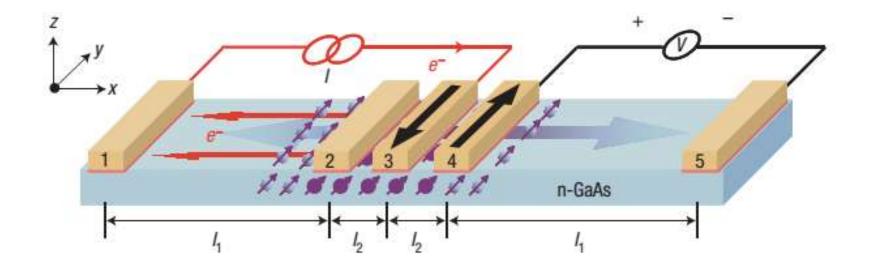
2) Insulating barrier, Al_2O_3 , MgO

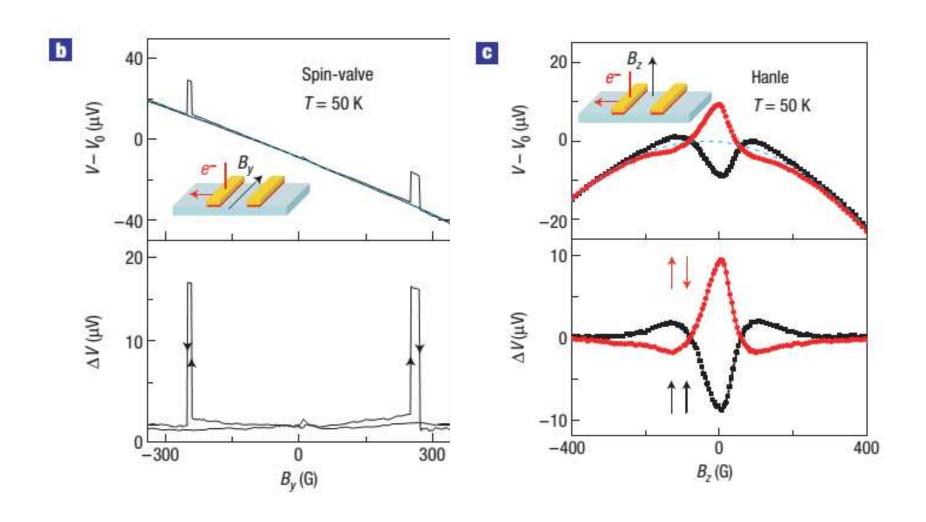


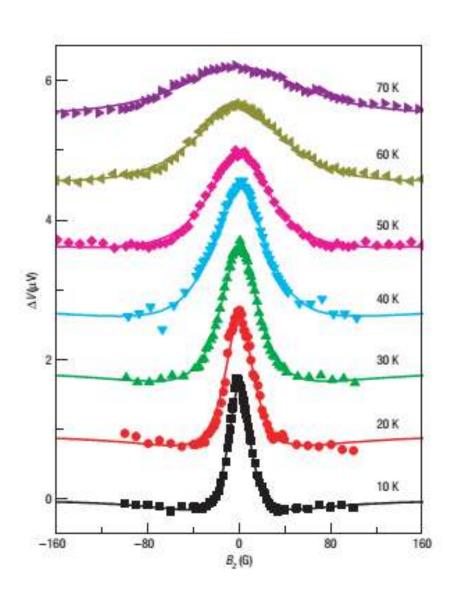




Lou, et al, PRL (2006)



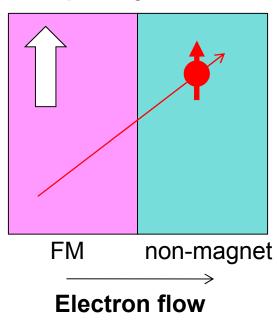




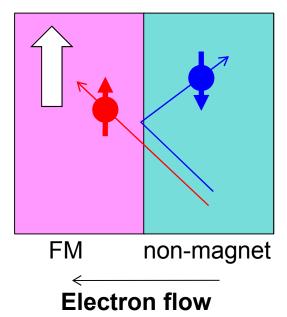
$$S_y(x_1, x_2, B) = S_0 \int_0^{\infty} \frac{1}{\sqrt{4\pi Dt}} e^{-(x_2-x_1-\nu_d t)^2/4Dt}$$

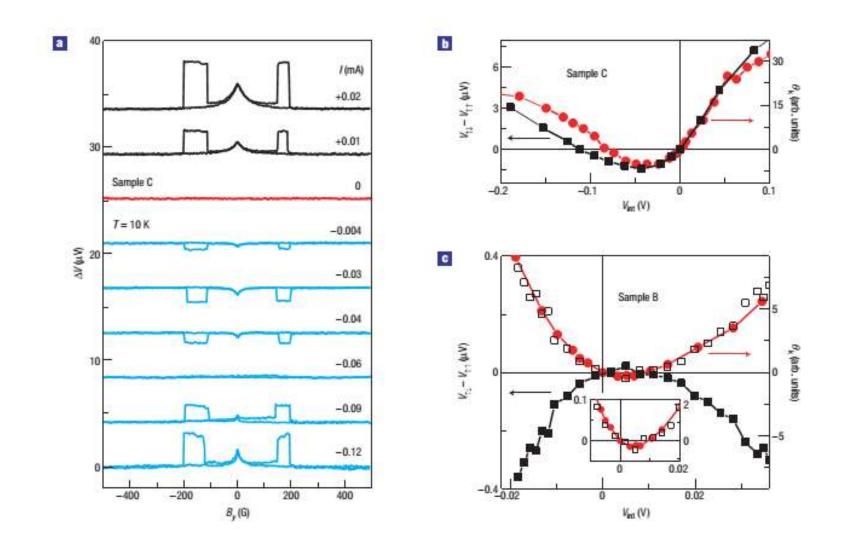
 $\times \cos(g\mu_B Bt/\hbar) e^{-t/\tau_a} dt$,

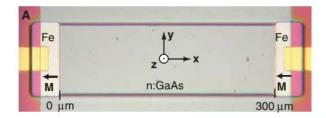
Spin Injection

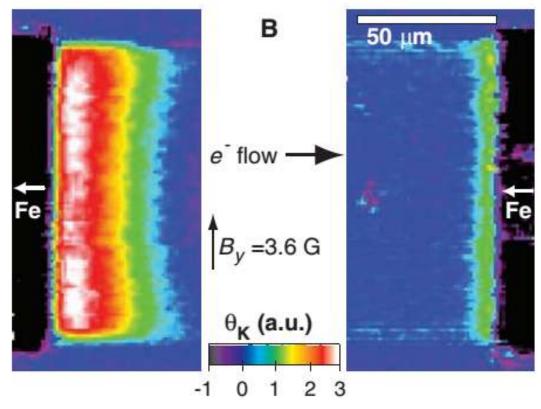


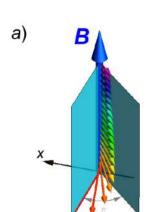
Spin Extraction / Reflection

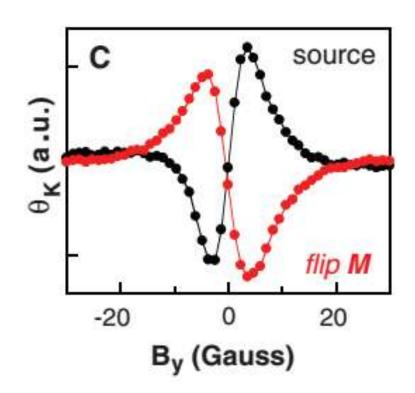


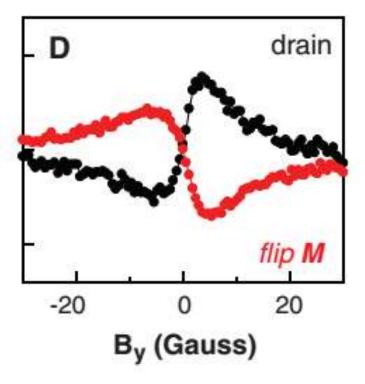


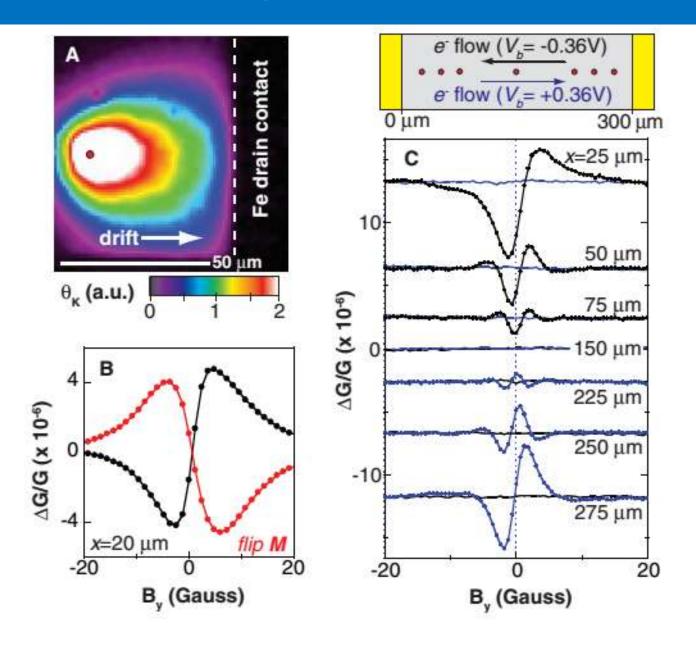


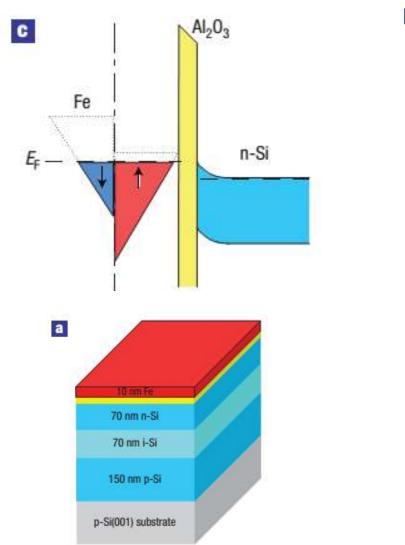


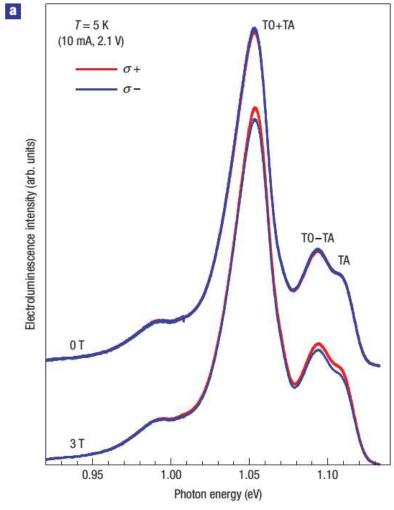




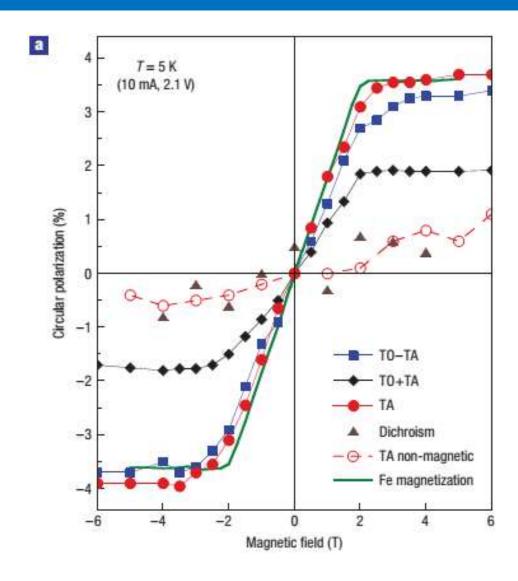


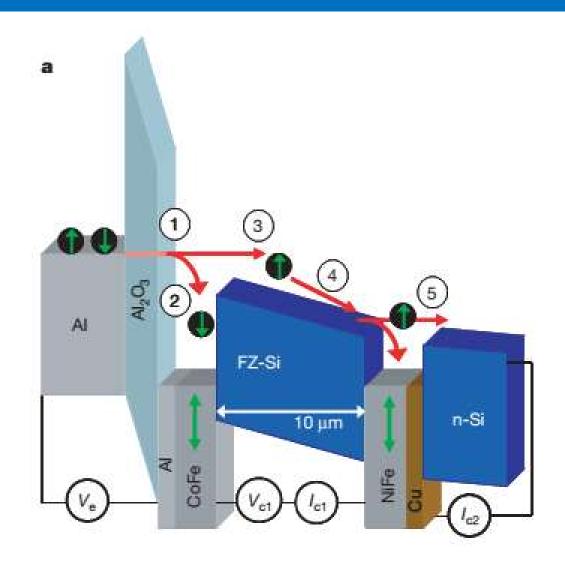


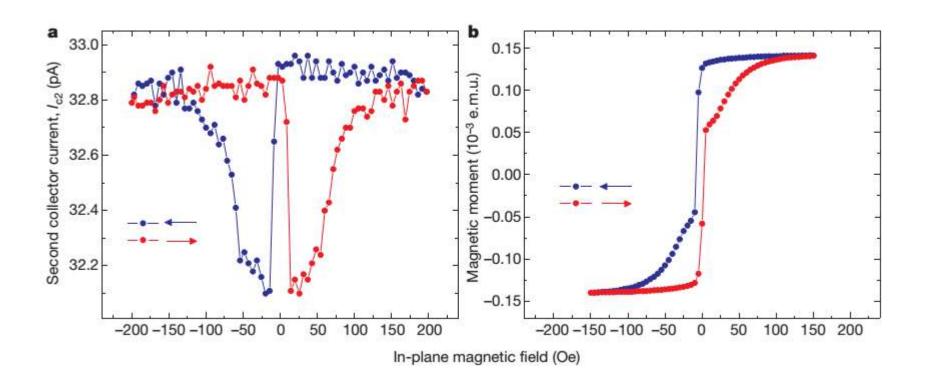


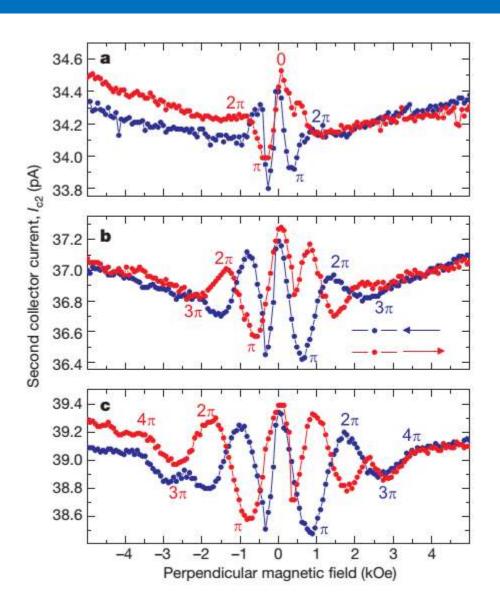


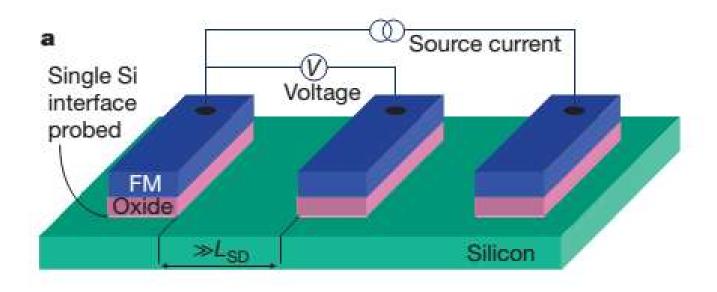
Jonker, et al, Nature Physics (2007)

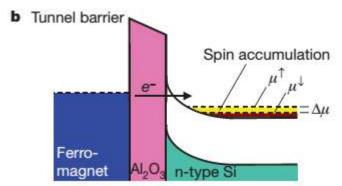




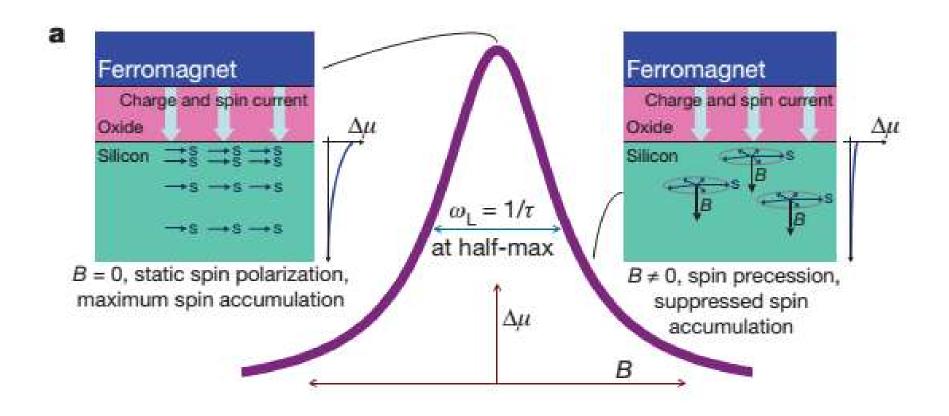


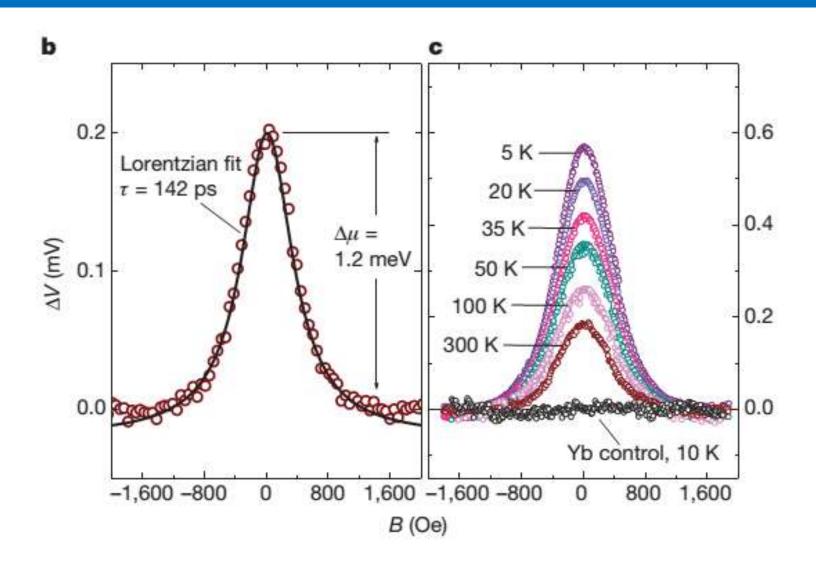




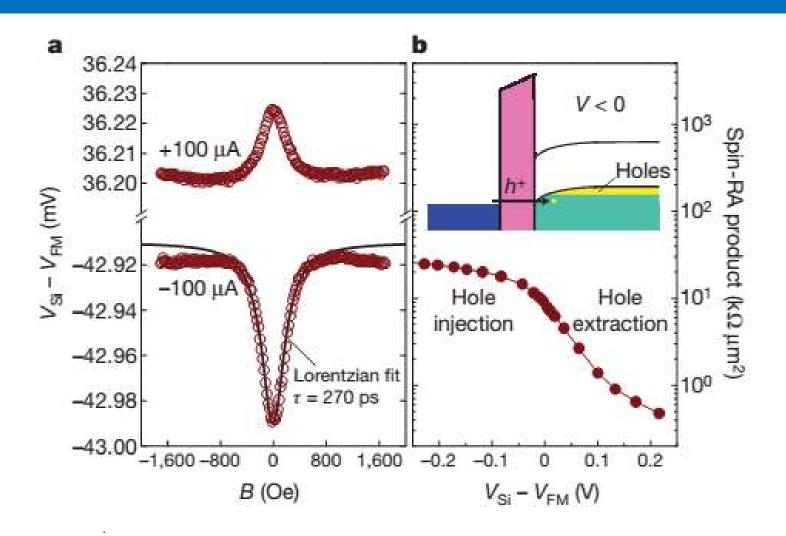


Dash, et al, Nature (2009)

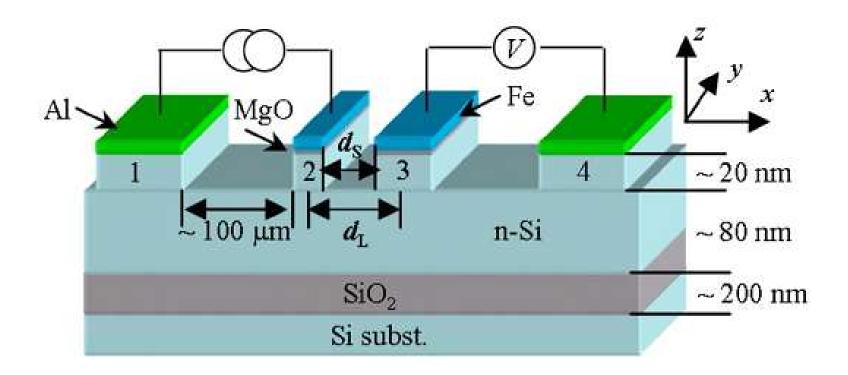




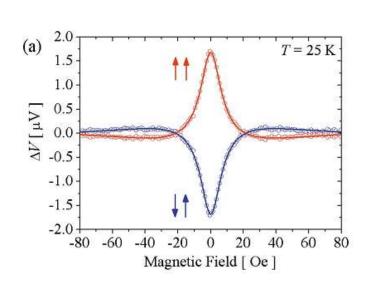
Spin in Silicon

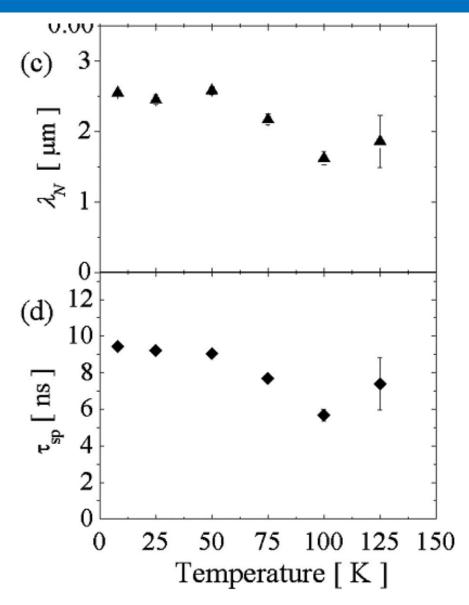


Spin in Silicon

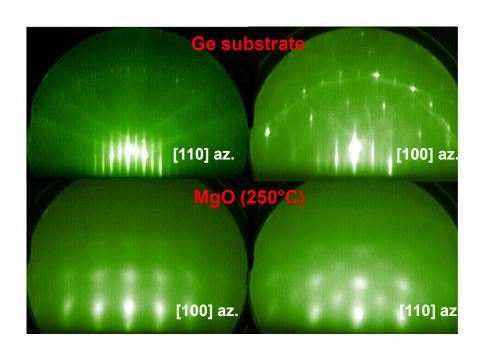


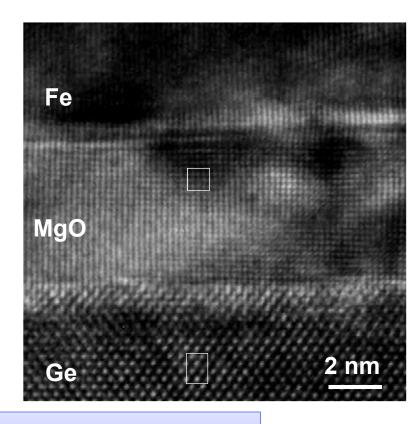
Spin in Silicon





Spin in Germanium

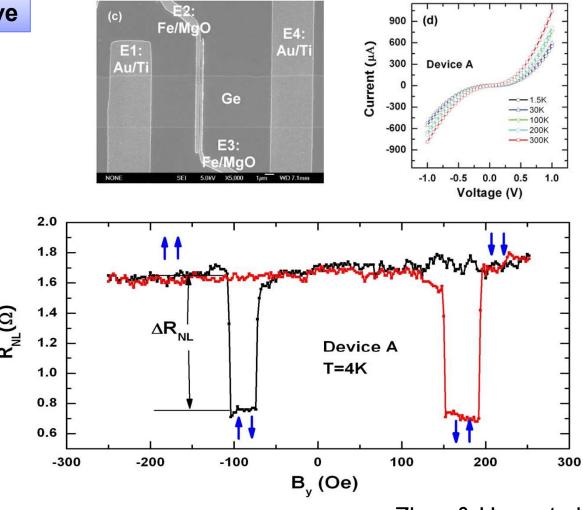




Epitaxial Fe/MgO/Ge junction is achieved MgO/Ge 45⁰ rotation

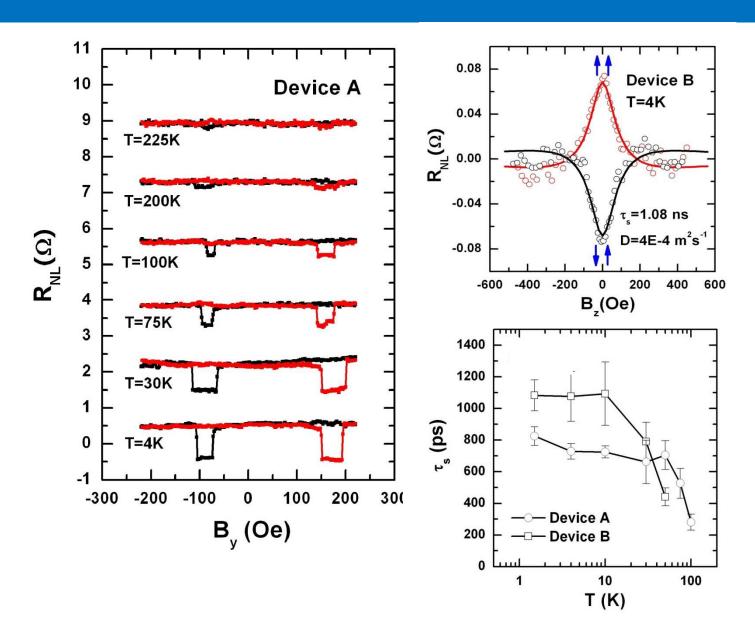
Spin in Germanium

Ge spin valve

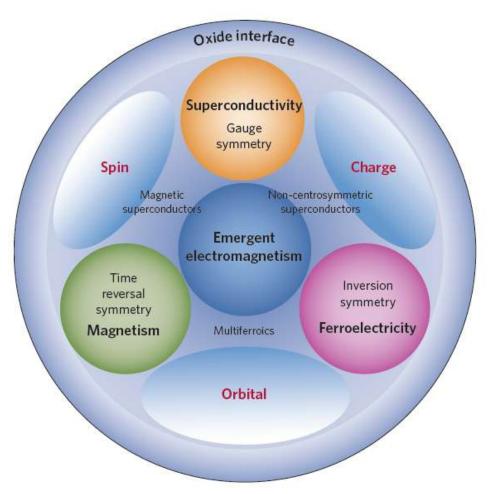


Zhou & Han, et al, PRB (2011)

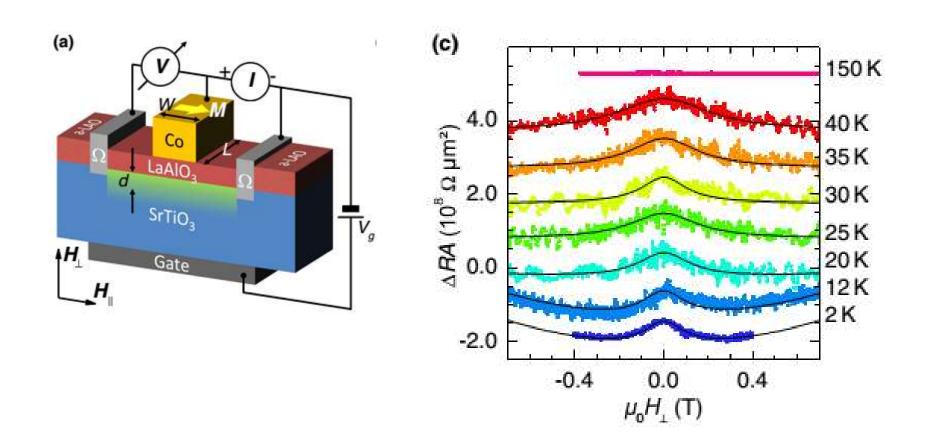
Spin in Germanium



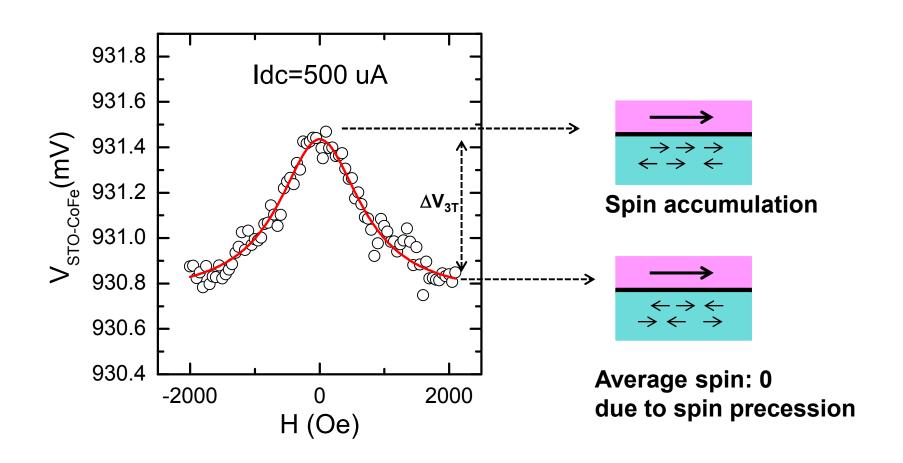
Oxide Interface



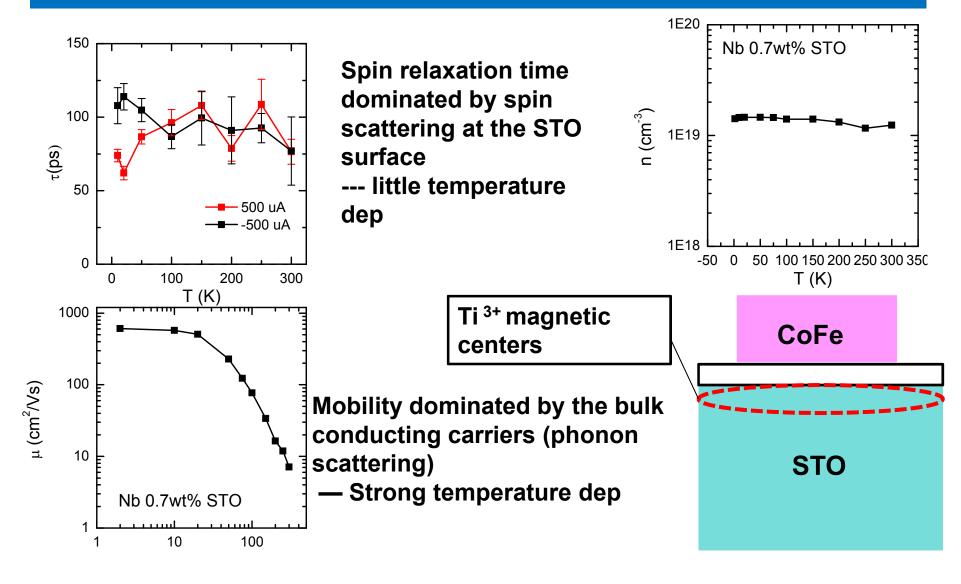
Hwang, et al. Nat. Mater. (2012)



Reyren, et al, PRL (2012)



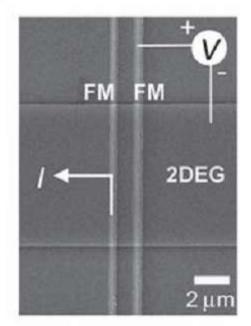
Han, et al, Nature Communications (2013)

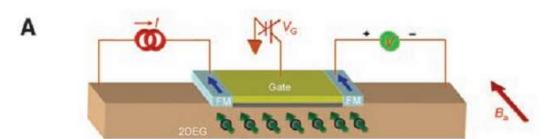


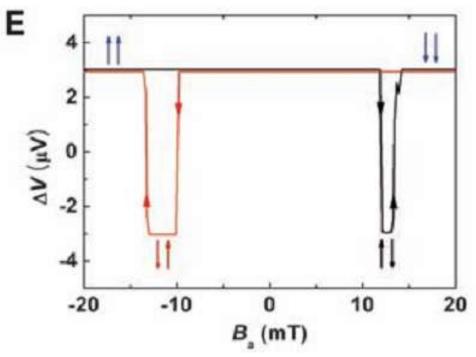
Spin FET



C

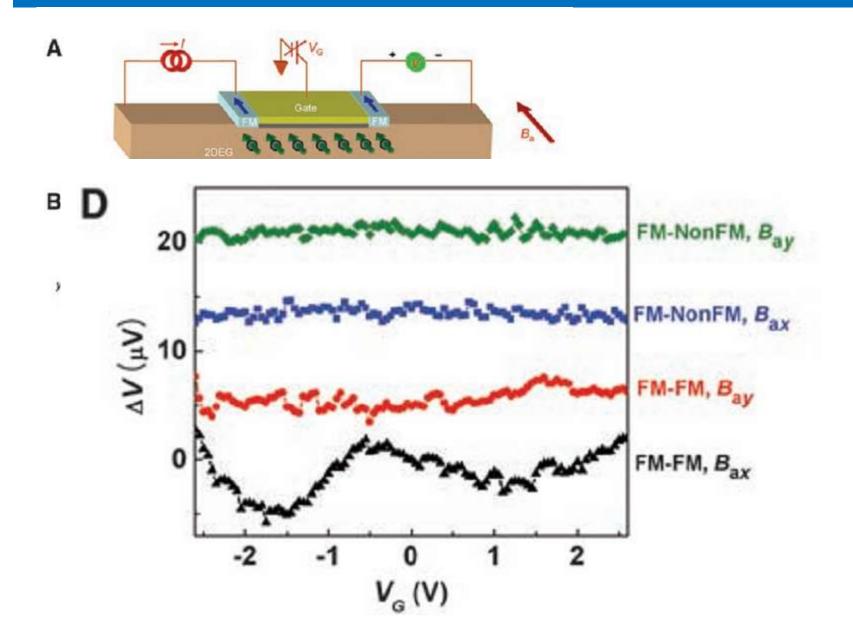




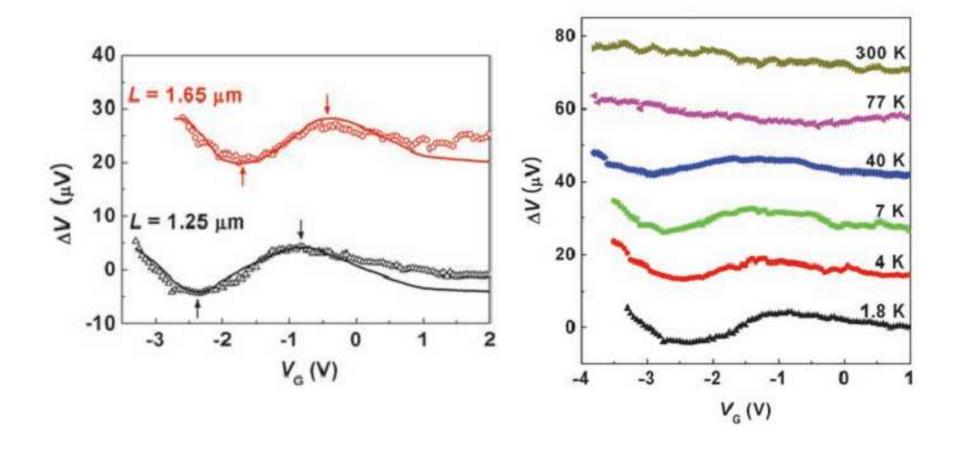


Koo, et al, Science (2009)

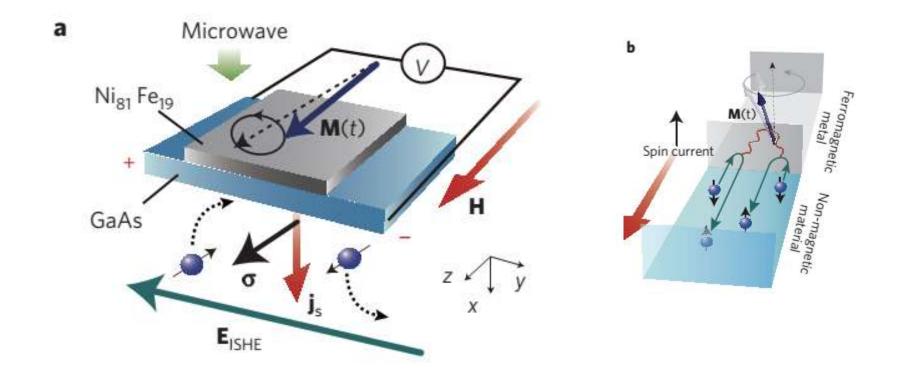
Spin FET



Spin FET

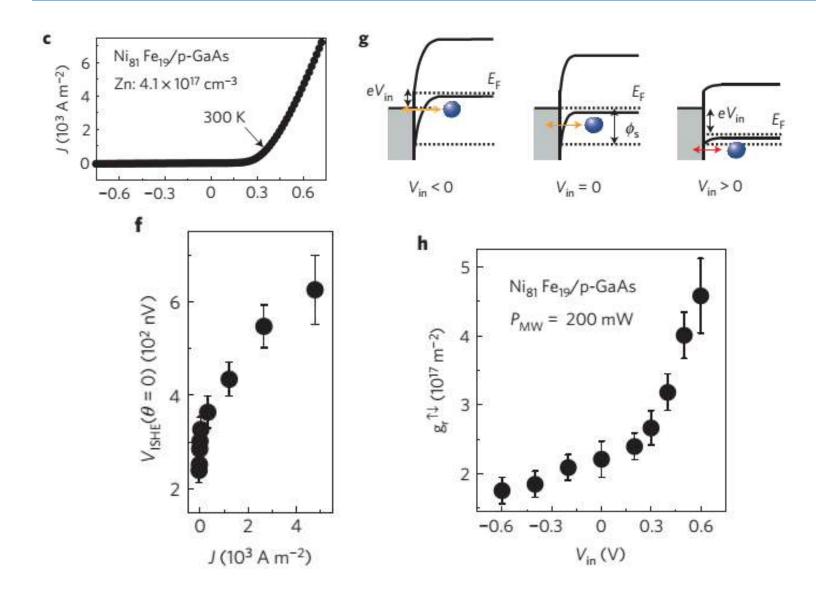


Another solution



Ando, et al, Nature Mater. (2011)

Another solution



休息10分钟

Outline 1 and 1 an

2. Spin valves based on Quantum materials

石墨烯

▶ 弱自旋-轨道耦合→ 长自旋寿命

二硫化钼等

▶ 自旋-谷

拓扑绝缘体

> 自旋流的拓扑保护

Graphene

Metals

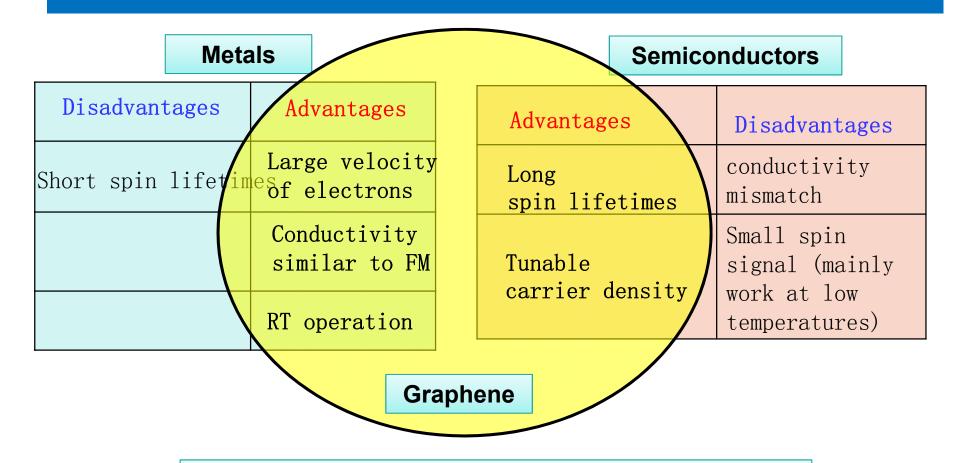
Disadvantages	Advantages
Short spin lifetime	Large velocity of electrons
	Conductivity similar to FM
	RT operation

Semiconductors

Advantages	Disadvantages
Long spin lifetimes	conductivity mismatch
Tunable carrier density	Small spin signal (mainly work at low temperatures)

55

Graphene

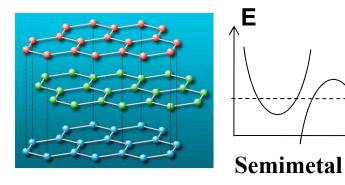


Graphene combines the advantages of both metals and semiconductors

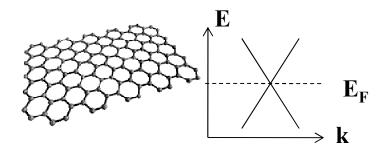
56

Graphene

Graphite



Graphene



Massless Dirac Fermions

Spin-dependent properties

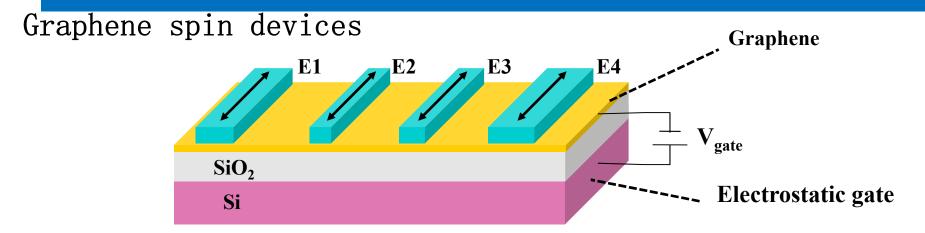
Low intrinsic spin-orbit coupling

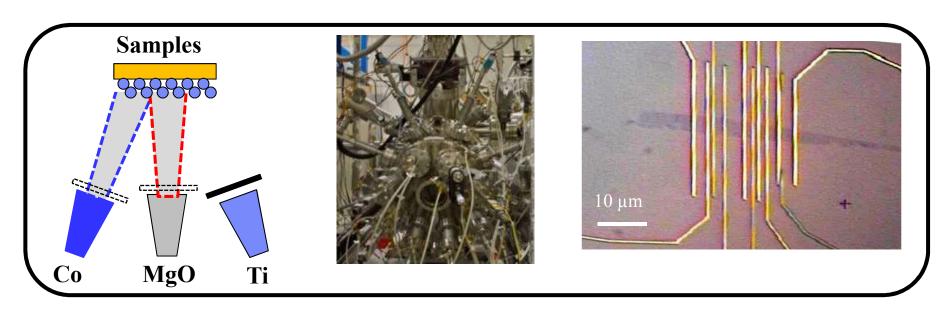
Long spin lifetime (~ μs)
High mobility

 $\lambda = \sqrt{D\tau}$

Long spin transport length

Gmitra, et al, *Phys. Rev. B* (2009) Abdelouahed, et al, *Phys. Rev. B* (2010)





$$\frac{\partial \vec{\mu}}{\partial t} = D \nabla^2 \vec{\mu} - \frac{\vec{\mu}}{\tau} + \left(\frac{g \mu_B}{\hbar} \vec{B} \times \vec{\mu} \right)$$

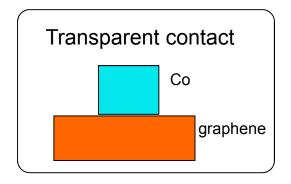
- 1) Diffusion D: diffusion constant
- 2) Relaxation τ : spin relaxation time
- 3) Larmor spin precession: $g \sim 2$

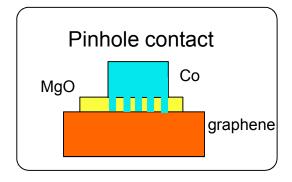
Spin relaxation length: $\lambda = \sqrt{D\tau}$

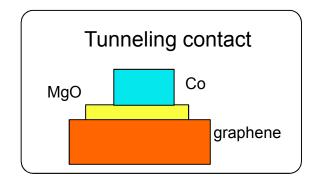
Diffuse without precession

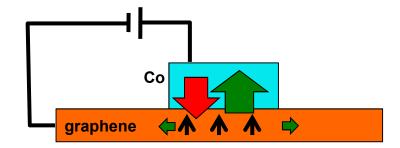
$$B_{\perp} = 0, \frac{\partial \mu}{\partial t} = 0,$$

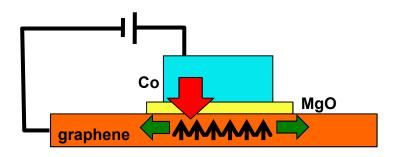
$$\mu(x) = \mu_0 \exp(-x/\lambda)$$



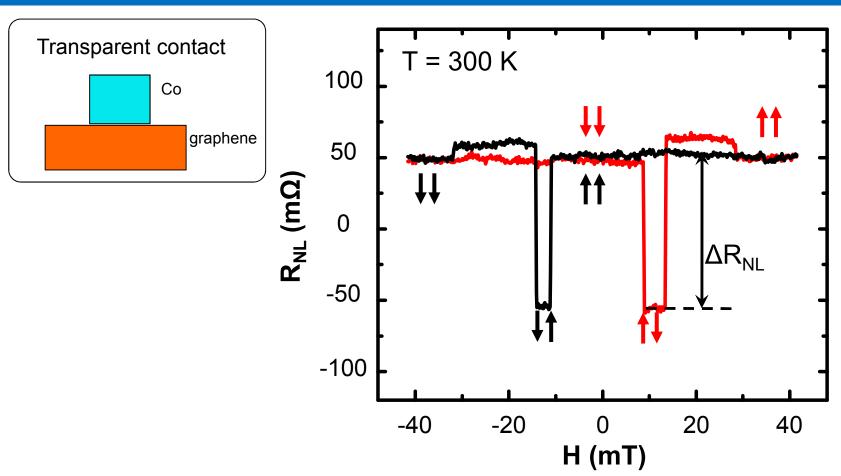






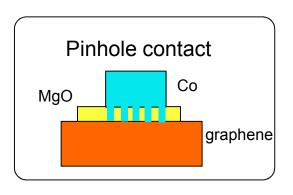


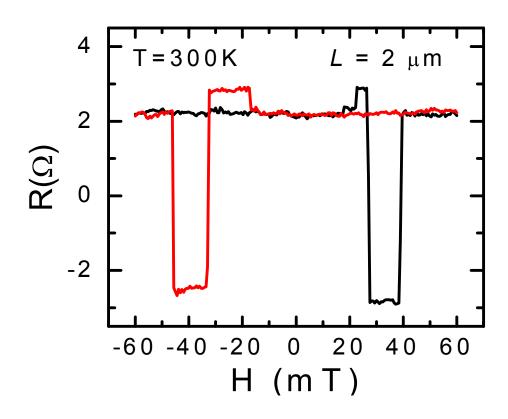
E.I. Rashba, Phys. Rev. B 62, R16 267 (2000) A. Fert, H. Jaffres, Phys. Rev. B 64, 184420 (2001).



Nonlocal MR: ~ 0.1 ohms

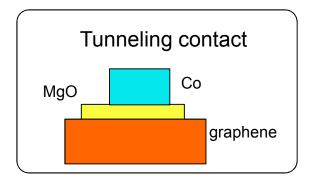
Spin injection efficiency: ~ 1 %

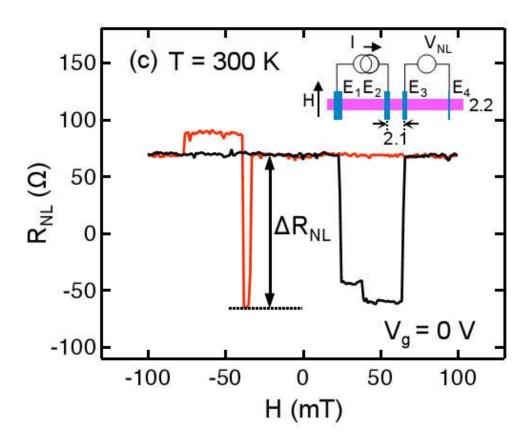




Nonlocal MR: ~ 10 ohms

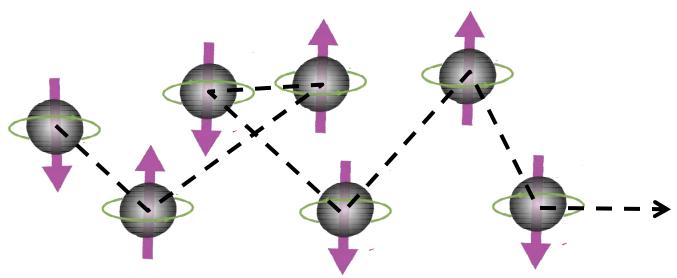
Spin injection efficiency: ~ 8 %





Nonlocal MR: ~130 ohms

Spin injection efficiency: ~ 30 %

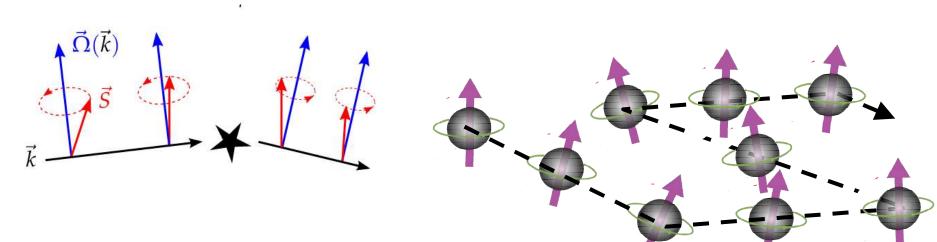


Spin flip during momentum scattering events: More momentum scattering, more spin relaxation.



J. Fabian, et al, Acta Phys. Slovaca (2007) R.J. Elliott, Phys. Rev. (1954) F. Meier and B.P. Zachachrenya, Optical Orientation, (1984). Josza, et al, Phys. Rev. B (2009)

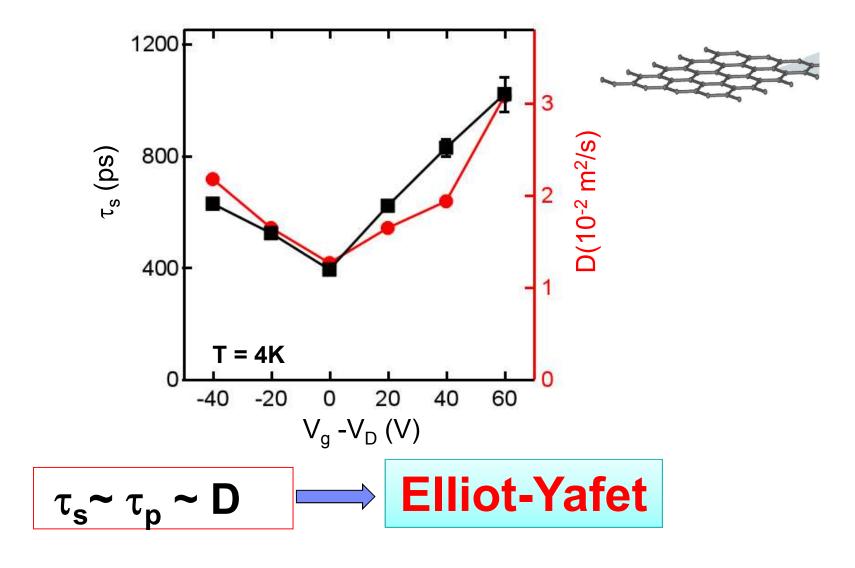
Momentum scattering can reduce this effect by randomizing the field

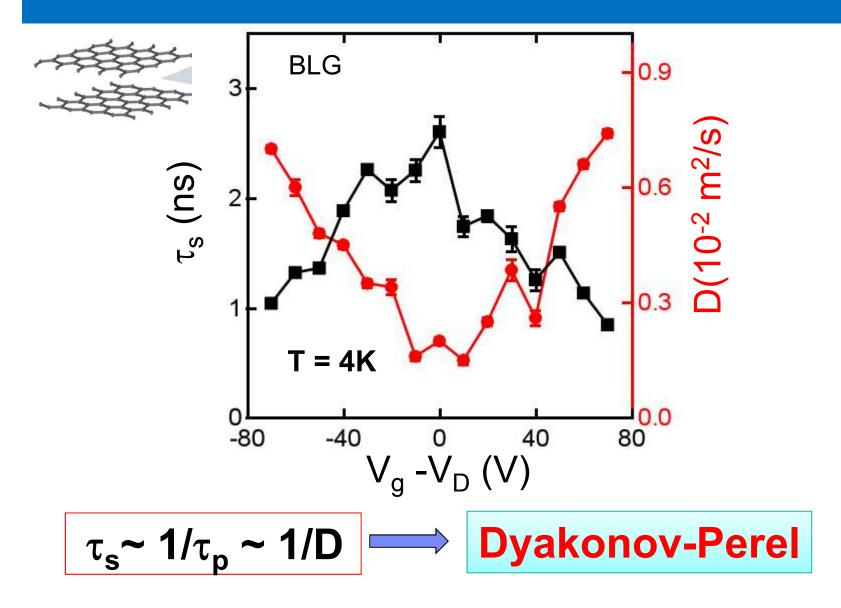


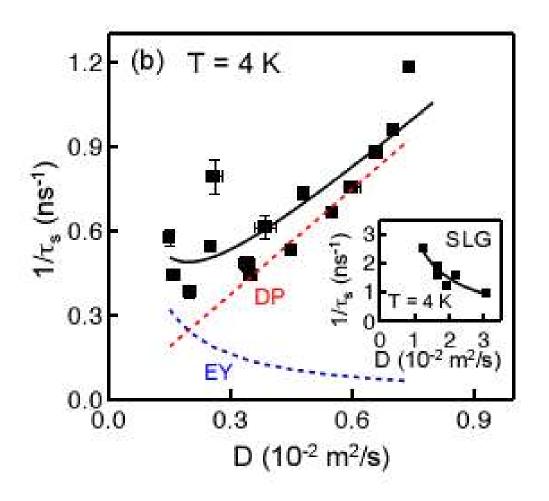
More momentum scattering, less spin relaxation



M. I. D'yakonov and V.I. Perel, Sov. Phys. Solid State (1972)







$$\frac{1}{\tau_{s}} = \frac{1}{\tau_{s}^{EY}} + \frac{1}{\tau_{s}^{DP}} = \frac{K_{EY}}{D} + K_{DP}D$$

BLG

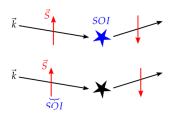
$$K_{EY} = 0.05 \pm 0.01 (10^{-2} \text{ m}^2\text{s}^{-1}) \text{ ns}^{-1}$$

 $K_{DP} = 1.24 \pm 0.09 (10^{-2} \text{ m}^2\text{s}^{-1})^{-1} \text{ ns}^{-1}$

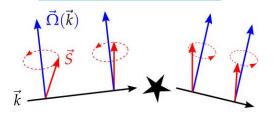
SLG

$$K_{EY}$$
 = 3.05 ± 0.35 (10⁻² m²s⁻¹)ns⁻¹
 K_{DP} = -0.02 ± 0.10 (10⁻² m²s⁻¹)⁻¹ns⁻¹

Elliot-Yafet



Dyakonov-Perel





Tombros, et al, Nature (2007)

Tombors, et al, PRL(2008)

Jozsa, et al, PRB (2009)

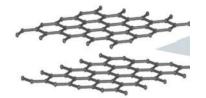
Han and Kawakami, PRL (2011)

~ 150 ps, impurity (EY)

Anisotropy (EY)

Linear scaling of $\lambda \& D$ (EY)

~1 ns, τ_s ~ $\tau_p(D)$ (EY)



Han and Kawakami, PRL (2011)

Yang, et al, PRL (2011)

Up to 6 ns, $\tau_s \sim 1/\tau_p(1/D)$ (DP)

Up to 2 ns, $\tau_s \sim 1/\mu$ (DP)

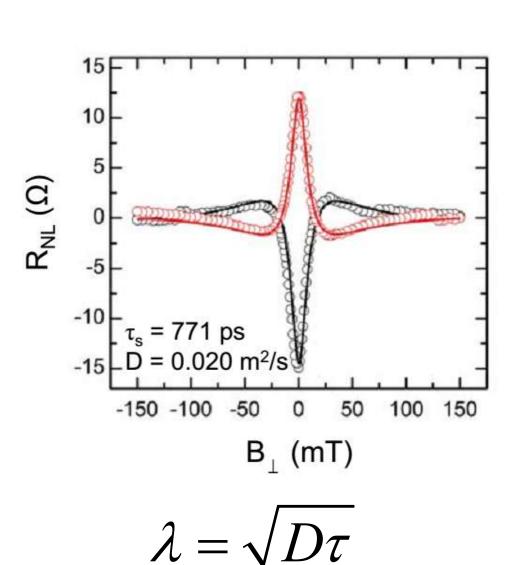
Being under investigation:

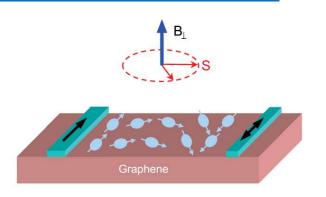
- Random Rashba field
- Magnetic resonant scattering

Wang and Wu, et al, NJP (2012)

Kochan, et al, arXiv:1306.0230 (2013)

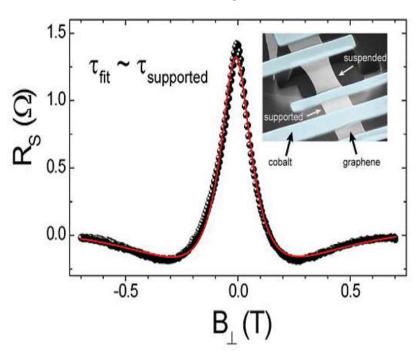
Spin diffusion length

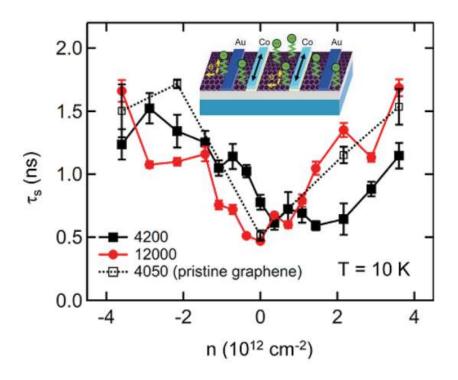




Spin diffusion length

Suspended graphene

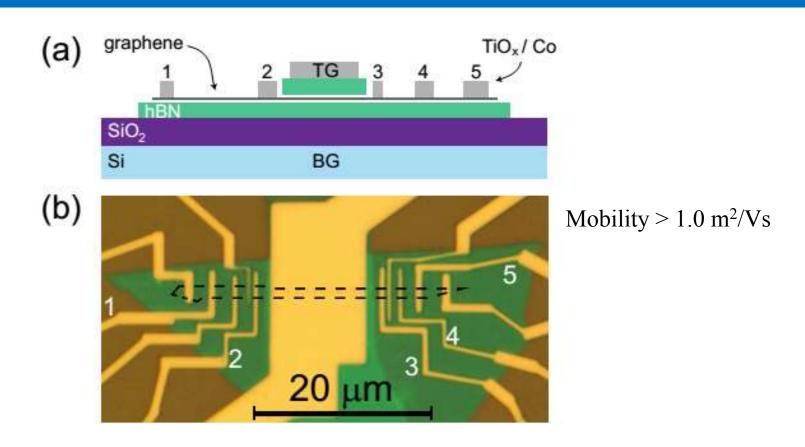




Spin diffusion lengths 1-5 microns

Guimarães, et al, Nano Letters (2012). Han, et al, Nano Letter (2012).

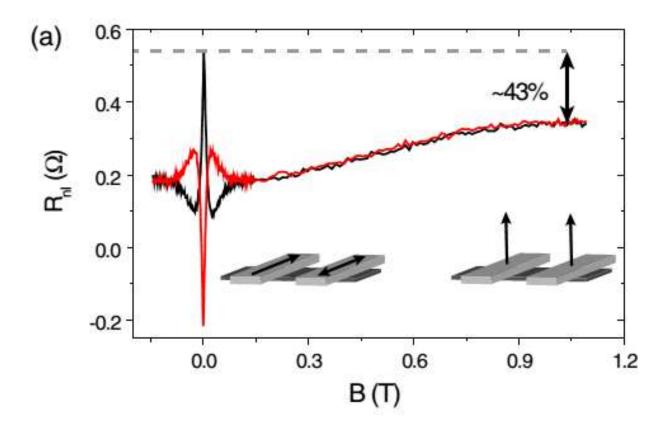
Spin diffusion length



Spin diffusion lengths >10 microns

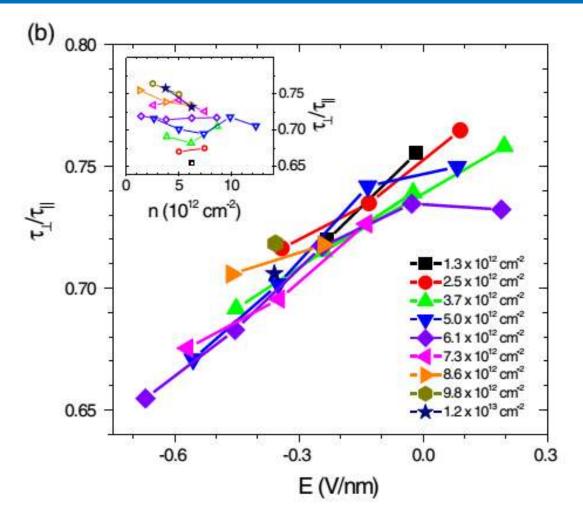
Guimarães, et al, PRL (2014) Drogeler, et al, Nano Letter (2014)

Anisotropy



Guimarães, et al, PRL (2014)

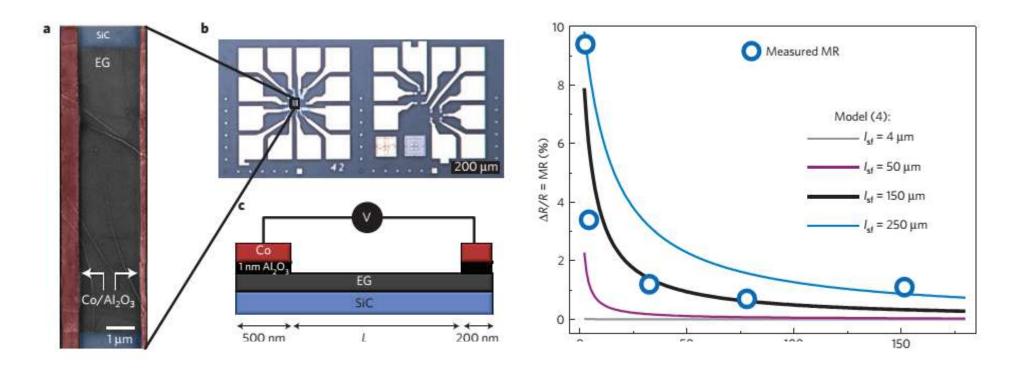
Anisotropy



Guimarães, et al, PRL (2014)

Spin diffusion length

An indirect method-- local MR measurement



Spin diffusion lengths >100 microns

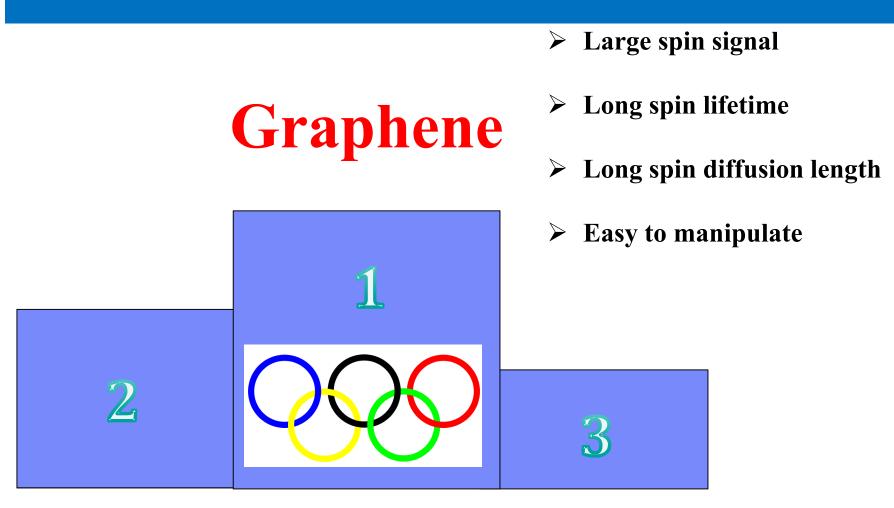
Spin properties of graphene

	Spin lifetime	Spin diffusion lengths	Spin signals
Room Temperature	0.5 - 2 ns	> 10 μm	130 Ω
Low Temperature	1 - 6 ns	> 10 μm (> 100 μm indirect)	1 MΩ for local MR

Spin properties of graphene

Spin Channel		Spin lifetime	Spin diffusion lengths	Spin signals	
Metals	Cu ^{15,131}	~ 42 ps at 4.2 K ~ 11 ps at 300 K	$\sim 1~\mu m$ at $4.2~K$ $\sim 0.4~\mu m$ at $300~K$	$\sim 1 \text{ m}\Omega$ at 4.2 K $\sim 0.5 \text{ m}\Omega$ at 300 K	
	Al ¹⁰⁸	~ 100 ps at 4.2 K ~ 45 ps at 300 K	~ 0.6 µm at 4.2 K ~ 0.4 µm at 300 K	\sim 12 m Ω at 4.2 K \sim 0.5 m Ω at 300 K	
	Ag ¹³²	~ 20 ps at 5 K ~ 10 ps at 300 K	~ 1 μm at 5 K ~ 0.3 μm at 300 K	$\sim 9 \text{ m}\Omega$ at 5 K $\sim 2 \text{ m}\Omega$ at 300 K	
Semiconductor	Highly doped Si ^{129,153}	~10 ns at 8 K ~1.3 ns at 300 K	~2 μm at 8 K ~0.5 μm at 300 K	~ 30 mΩ at 8 K ~ 1 mΩ at 300 K	
	GaAs ¹⁵⁴	24 ns at 10 K 4 ns at 70 K	6 μm at 50 K	~ 30 mΩ at 50 K	
	Highly doped Ge ¹³⁰	~ 1 ns at 4 K ~ 300 ps at 100 K	~ 0.6 µm at 4 K	0.1-1 Ω at 4 K 0.02 ~ 0.1 Ω at 200 K	
Graphene ⁶	.9.10	0.5 - 2 ns at 300 K 1 - 6 ns at 4 K	3 - 10 μm at 300 K (~100 μm fit from local MR data)	130 Ω at 300 K (1 MΩ for local MR at 1.4 K)	

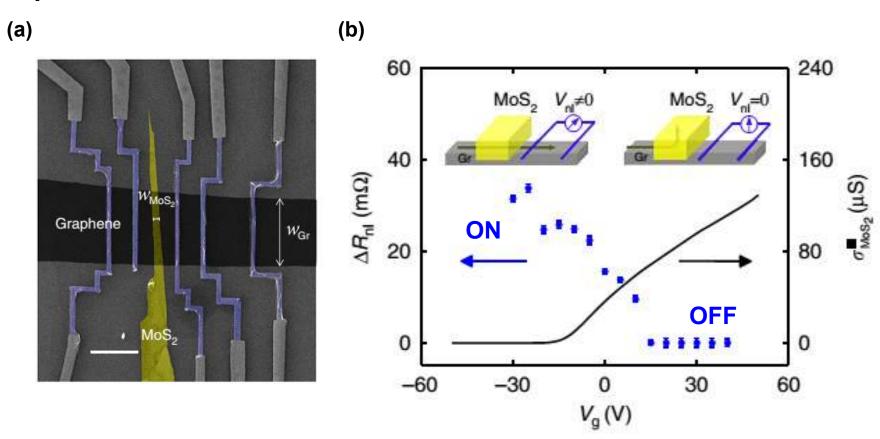
Spin properties of graphene



Han, et al, Nature Nanotechnology (2014)

Graphene spin transistor

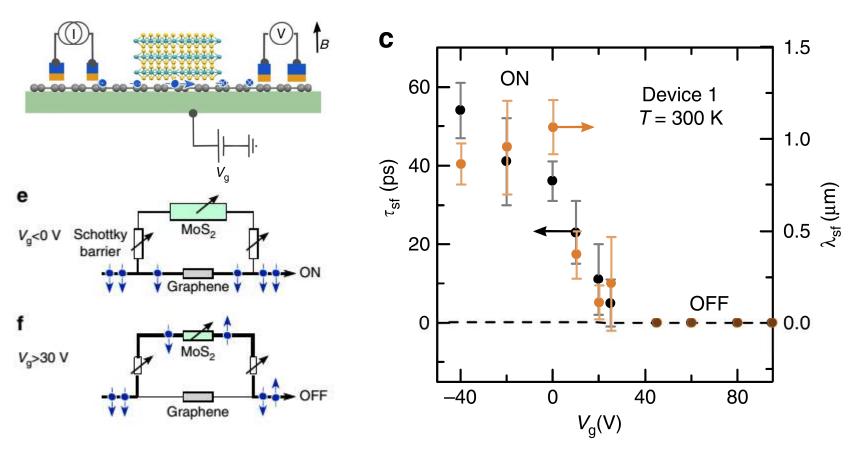
Graphene/MoS2 channel



Yan, et al, *Nat. Commun.* 7, 13372 (2016). Dankert and Dash, *Nat. Commun.* 8, 16093 (2017).

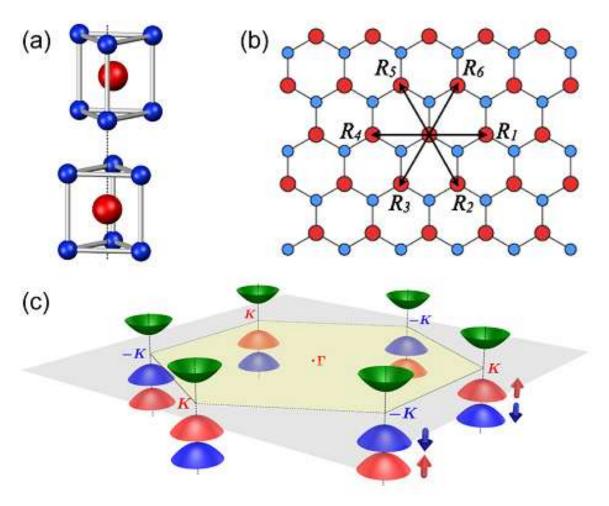
Graphene spin transistor

Graphene/MoS2 channel: gate tuning the channel and spin lifetimes

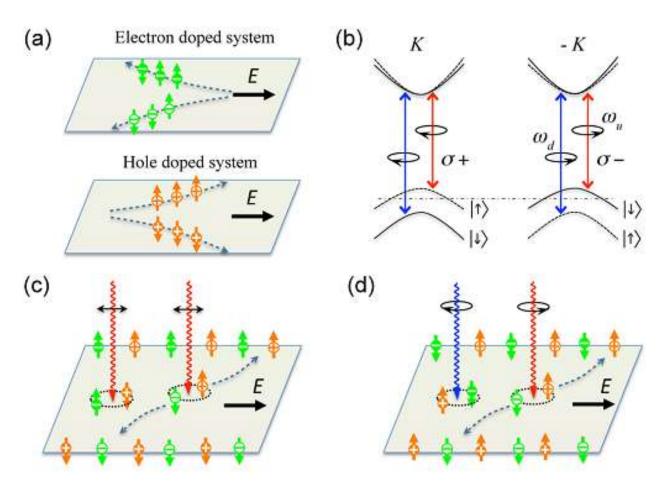


Yan, et al, *Nat. Commun.* 7, 13372 (2016). Dankert and Dash, *Nat. Commun.* 8, 16093 (2017).

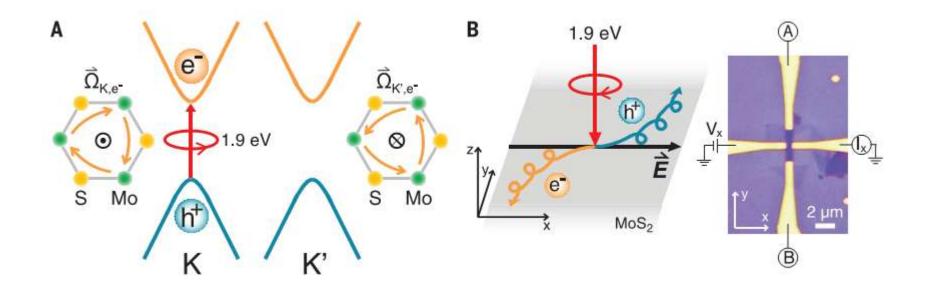
MoS2

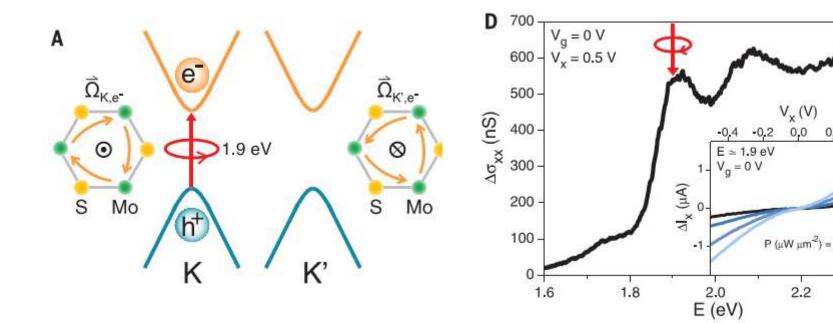


Xiao, et al, PRL (2013)



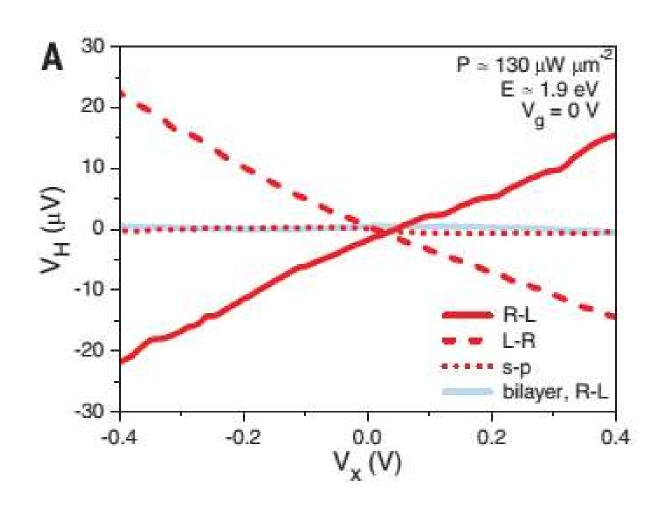
Xiao, et al, PRL (2013)

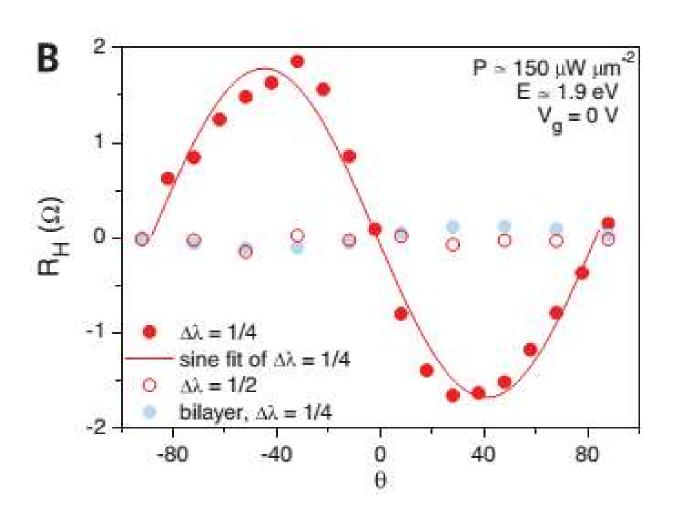




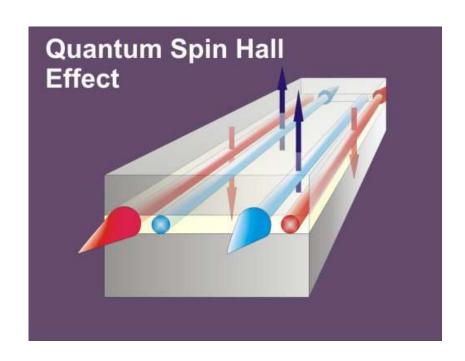
2.4

0.2

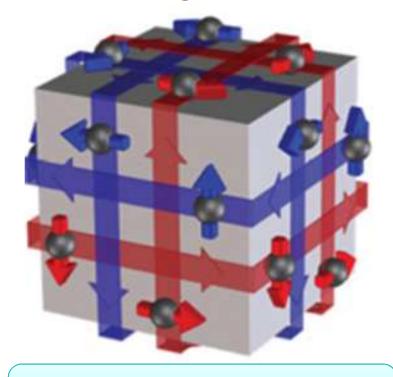




Topological insulators—Spin-Momentum locking

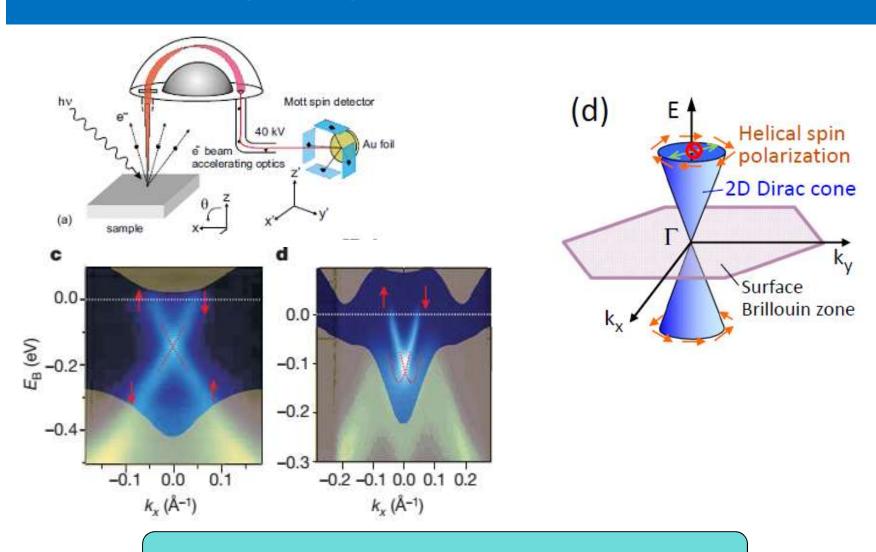


2D Topological insulator

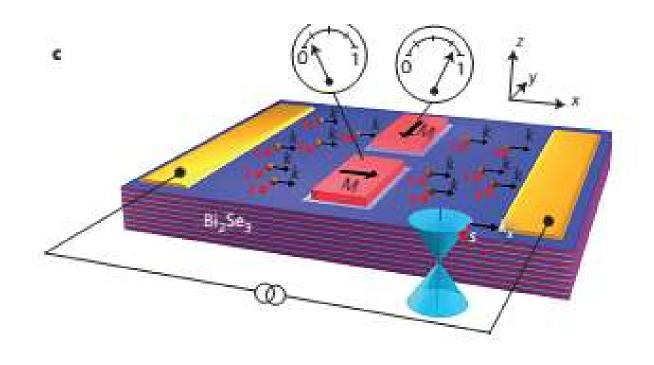


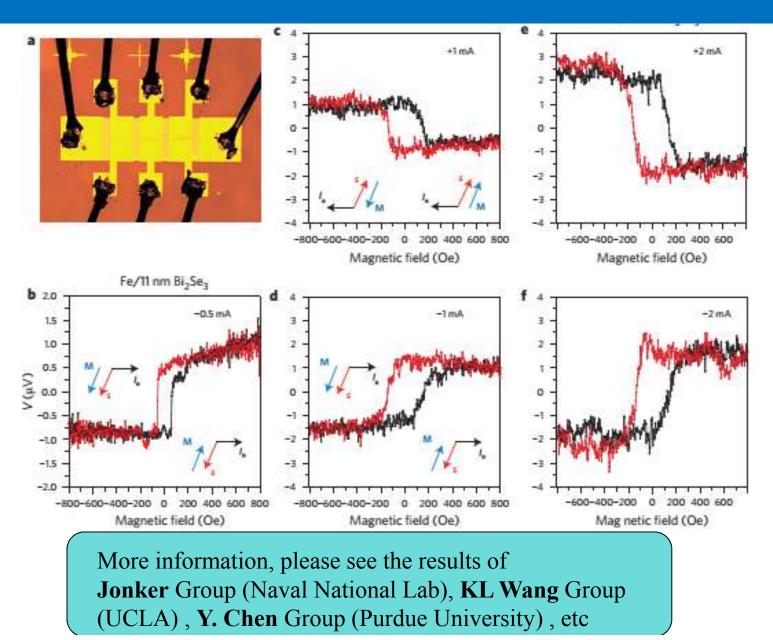
3D Topological insulator

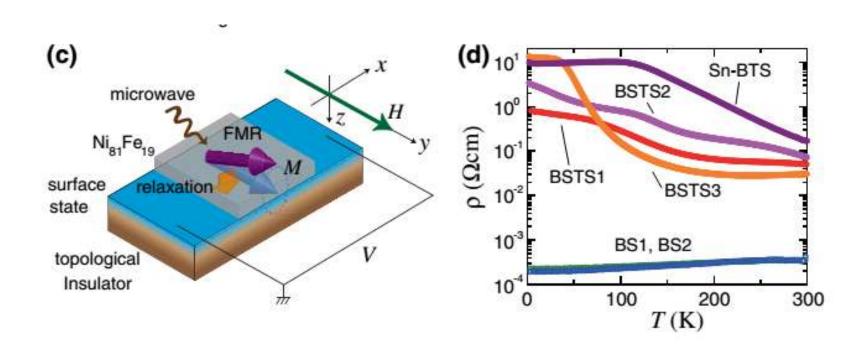
Qi&Zhang, *Rev. Mod. Phys.* (2011) Hasan& Kane, *Rev. Mod. Phys.* (2010) Yazyev, et al, Phys. Rev. Lett. (2010).

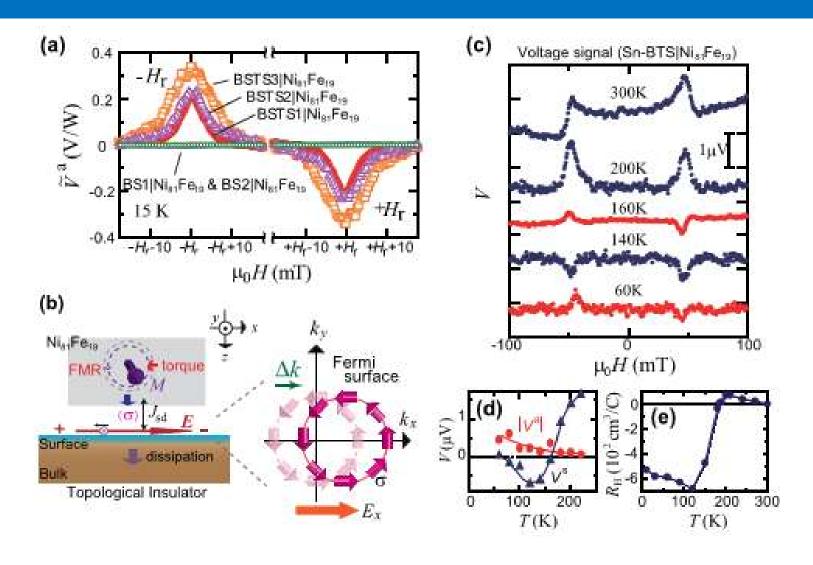


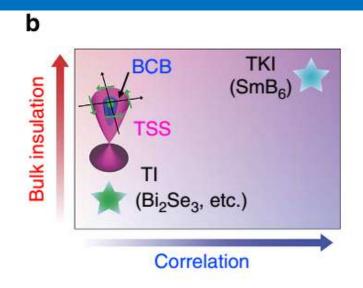
Spin ARPES: Hasan Group (Priceton University)

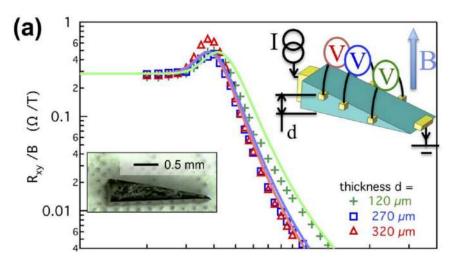


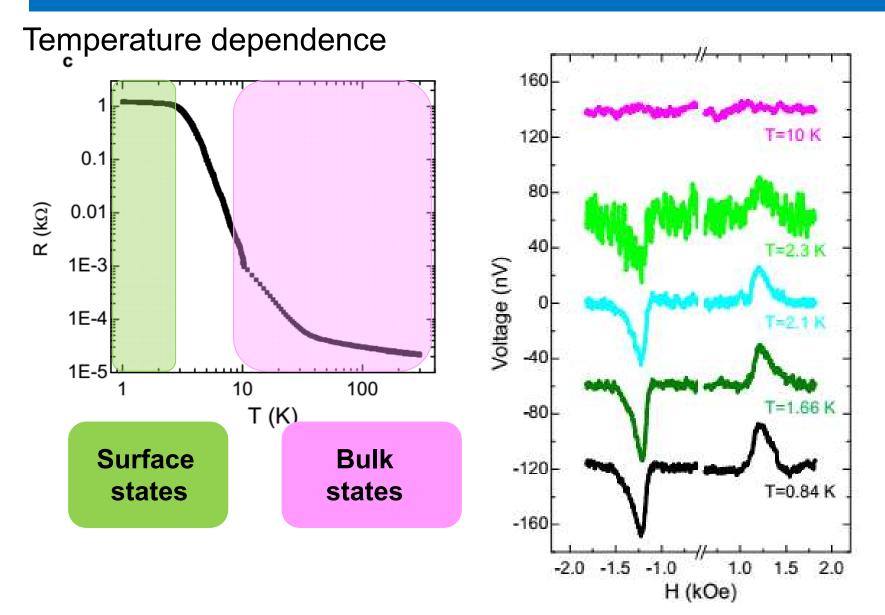


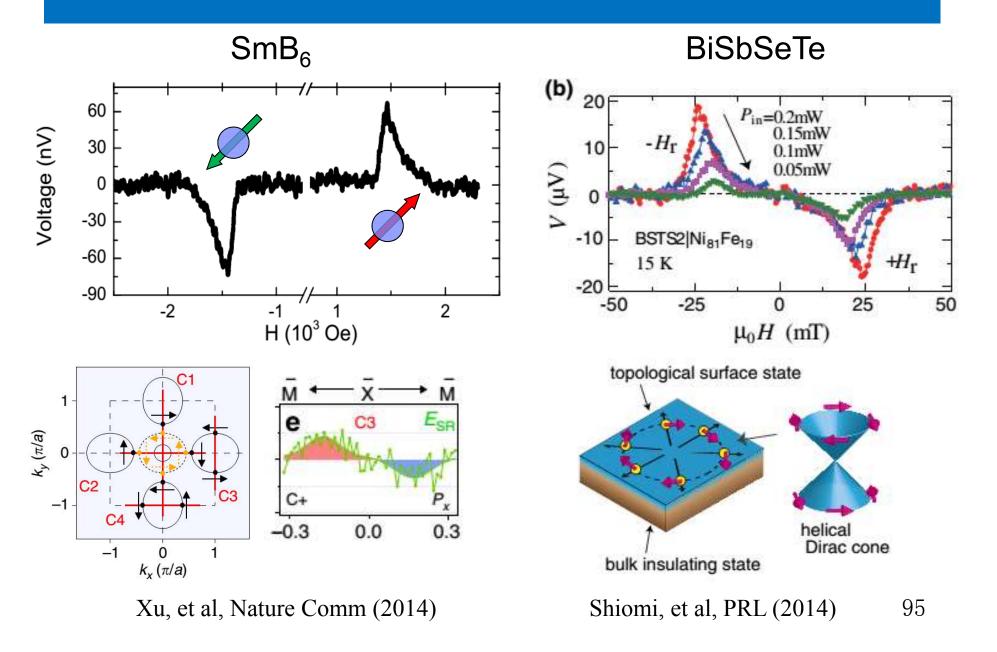












Summary

1. Semiconductor Spin Valves

When spintronics meets semiconductor

GaAs

Silicon and Germanium

Complex oxides

Spin FET

Summary

2. Spin valves based on Quantum materials

石墨烯

▶ 弱自旋-轨道耦合→ 长自旋寿命

二硫化钼等

▶ 自旋-谷

拓扑绝缘体

> 自旋流的拓扑保护

下一节课: Nov. 16th

Chapter 5: Spin transfer torque

课件下载:

http://www.phy.pku.edu.cn/~LabSpin/teaching.html